

AMENDMENTS TO THE CLAIMS

Please rewrite the claims as follows:

1. (Canceled)

2. (Currently Amended) An exposure apparatus according to ~~claim 1~~ claim 7, wherein the first and second drives provide the reflective element with the displacements, and a minimum unit of a displacement amount by said second driver is smaller than that by said first driver.

3. (Currently Amended) An exposure apparatus according to ~~claim 1~~ claim 7, wherein a minimum unit of a displacement amount by said first driver is larger than double of a minimum unit of a displacement amount by said second driver.

4. (Currently Amended) An exposure apparatus according to ~~claim 1~~ claim 7, wherein said second driver has higher control precision than said first driver.

5. (Currently Amended) An exposure apparatus according to ~~claim 1~~ claim 7, wherein said second driver has a higher control frequency than said first driver.

6. (Currently Amended) An exposure apparatus according to ~~claim 1~~ claim

7, further comprising:

a first measurement unit for measuring a displacement amount of the
reflective element by said first driver; and

a second measurement unit for measuring a displacement amount of the
reflective element by said second driver.

7. (Currently Amended) An exposure apparatus ~~according to claim 1~~, ~~further~~
comprising:

a reflective element for reflecting and introducing light from a light source
to a plate;

at least one first driver for providing the reflective element with a force
and/or a displacement in at least one directions;

at least one second driver for providing the reflective element with a force
and/or a displacement in at least one directions, wherein said first and second
drives are connected in series to each other;

a first measurement unit for measuring a relative position between one
end and another end of said first driver; and

a second measurement unit for measuring a relative position between one
end and another end of said second driver.

8. (Currently Amended) An exposure apparatus according to ~~claim 1~~ claim 7, wherein said exposure apparatus is a scanning exposure apparatus that provides exposure by relatively scanning the original form and the plate.

9. (Currently Amended) An exposure apparatus according to ~~claim 1~~ claim 7, wherein an optical path from the light source to the plate is maintained substantially vacuum.

10. (Currently Amended) An exposure apparatus according to ~~claim 1~~ claim 7, wherein the light from the light source has a wavelength between 13 and 14 nm.

11. (Currently Amended) An exposure apparatus ~~according to claim 1, further~~ comprising:

a reflective element for reflecting and introducing light from a light source to a plate;

at least one first driver for providing the reflective element with a force and/or a displacement in at least one directions;

at least one second driver for providing the reflective element with a force and/or a displacement in at least one directions, wherein said first and second drives are connected in series to each other;

a projection optical system, provided with said reflective element, for

introducing to the plate light from the pattern illuminated by the light from the light source; and

a wave front aberration measurement unit for measuring wave front aberration in said projection optical system, wherein the reflective element is driven based on a measurement result by said wave front aberration measurement unit.

12. (Currently Amended) An exposure apparatus ~~according to claim 1, further~~ comprising:

a reflective element for reflecting and introducing light from a light source to a plate;

at least one first driver for providing the reflective element with a force and/or a displacement in at least one directions;

at least one second driver for providing the reflective element with a force and/or a displacement in at least one directions, wherein said first and second drives are connected in series to each other;

a projection optical system, provided with said reflective element, for introducing to the plate light from the pattern illuminated by the light from the light source;

a wave front aberration measurement unit for measuring wave front aberration in said projection optical system; and

a corrective drive amount calculator for calculating a corrective drive

amount for the reflective element based on a measurement value by the wave front aberration measurement unit.

13. (Currently Amended) An exposure apparatus ~~according to claim 11~~
comprising:

a reflective element for reflecting and introducing light from a light source to a plate;

at least one first driver for providing the reflective element with a force and/or a displacement in at least one directions;

at least one second driver for providing the reflective element with a force and/or a displacement in at least one directions, wherein said first and second drives are connected in series to each other;

a projection optical system, provided with said reflective element, for introducing to the plate light from the pattern illuminated by the light from the light source; and

a wave front aberration measurement unit for measuring wave front aberration in said projection optical system, wherein the reflective element is driven based on a measurement result by said wave front aberration measurement unit,

wherein said projection optical system includes plural reflective elements, and the corrective drive amount is selectively provided to the plural reflective elements.

14. (Currently Amended) An exposure apparatus ~~according to claim 11~~

comprising:

a reflective element for reflecting and introducing light from a light source
to a plate;

at least one first driver for providing the reflective element with a force
and/or a displacement in at least one directions;

at least one second driver for providing the reflective element with a force
and/or a displacement in at least one directions, wherein said first and second
drives are connected in series to each other;

a projection optical system, provided with said reflective element, for
introducing to the plate light from the pattern illuminated by the light from the
light source; and

a wave front aberration measurement unit for measuring wave front
aberration in said projection optical system, wherein the reflective element is
driven based on a measurement result by said wave front aberration measurement
unit,

further comprising a stage for mounting and driving the plate, wherein said wave
front aberration measurement unit is provided on the stage.

15. (Currently Amended) An exposure apparatus ~~according to claim 11~~

comprising:

a reflective element for reflecting and introducing light from a light source

to a plate;

at least one first driver for providing the reflective element with a force
and/or a displacement in at least one directions;

at least one second driver for providing the reflective element with a force
and/or a displacement in at least one directions, wherein said first and second
drives are connected in series to each other;

a projection optical system, provided with said reflective element, for
introducing to the plate light from the pattern illuminated by the light from the
light source; and

a wave front aberration measurement unit for measuring wave front
aberration in said projection optical system, wherein the reflective element is
driven based on a measurement result by said wave front aberration measurement
unit,

further comprising a stage for mounting and driving the original form, wherein
said wave front aberration measurement unit is provided on the stage.

16. (Currently Amended) A device fabrication method comprising the steps
of:

exposing a plate using an exposure apparatus; and

developing the plate that has been exposed,

wherein the exposure apparatus includes:

an illumination optical system for illuminating a pattern on an original

form using light from a light source;

a projection optical system for introducing light from the pattern on the original form to the plate;

at least one first driver for providing a reflective element that reflects light from the light source to the plate, with a force and/or a displacement in at least one directions; ~~and~~

at least one second driver for providing the reflective element with a force and/or a displacement in at least one directions;

a first measurement unit for measuring a relative position between one end and another end of said first driver; and

a second measurement unit for measuring a relative position between one end and another end of said second driver.

17-21. (Canceled)